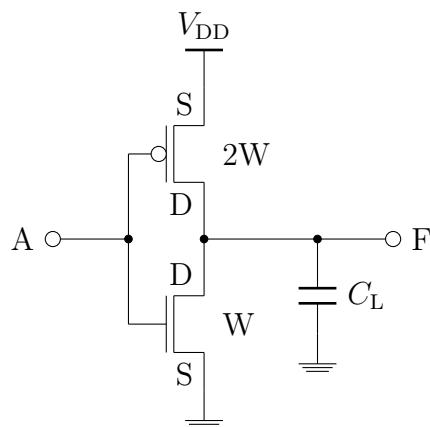


Task 7.1**Figure 7.1:** Sizing a CMOS Inverter

Design a NAND3 and NOR3 gate in CMOS. It is assumed that all transitions are to be sized according to the inverter in Fig. 7.1.

Task 7.2

Provide two additional multi-level implementations of an AND8 gate.

Task 7.3

- Calculate the switching voltage V_S of a NAND2 (Fig. 7.2). Boundary conditions are:
 - exactly one input is connected to V_{DD} , the other input performs a transition from 0 to V_{DD} ;
 - both inputs are connected to each other.

Assumption: 0.18 μm technology parameter, $W_N = W_P = 400\text{nm}$.

- Use SPICE to compare the voltage transfer characteristics (V_S) of the two above cases of a NAND2. Also, assume that the A and B inputs each switch independently. Why are the results different?

Task 7.4

Given is the expression

$$F = \overline{AB + CD}.$$

Implement it as single-level CMOS complex as well as pseudo-NMOS.

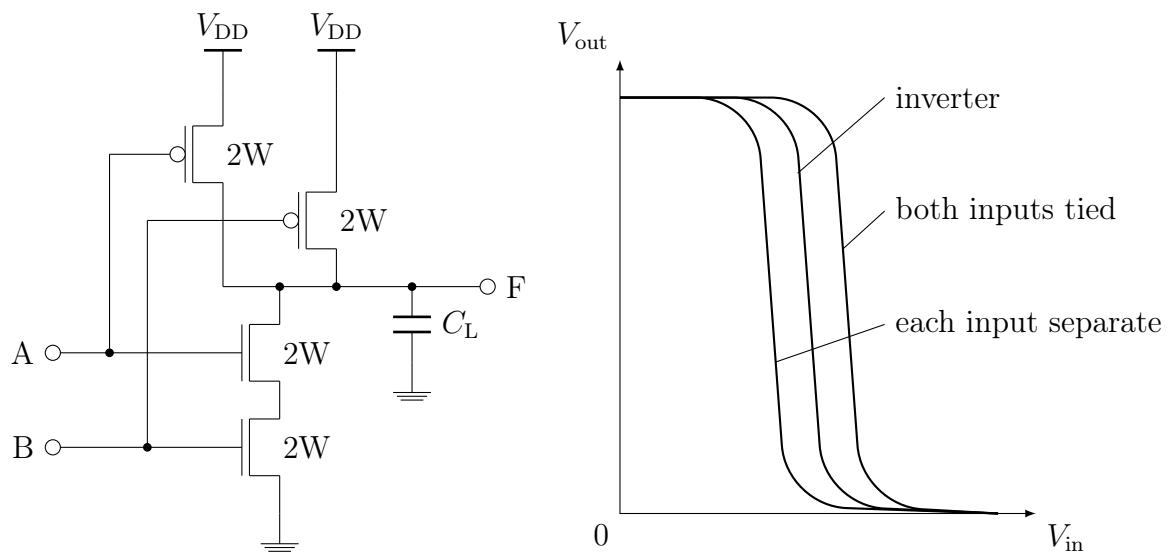


Figure 7.2: Voltage Transmission Characteristics (VTC) of NAND2

Task 7.5

Design the logical function for the circuit in Fig. 7.3. What is the worst case for the voltages V_{OH} and V_{OL} ? Assume a load capacitance of 100fF at the output. What does this influence the logical values High (H) and Low (L)?

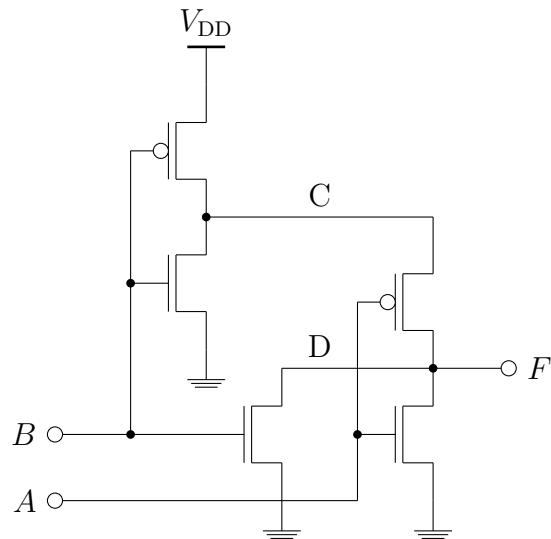


Figure 7.3: Schematic of a digital circuit

Task 7.6

Design a RS Latch in $0.13\mu\text{m}$ CMOS technology ($\mu_n = 270\text{cm}^2/\text{Vs}$, $C_{\text{ox}} = 1.6\mu\text{F}/\text{cm}^2$, $V_{TN} = 0.4\text{V}$, $V_{TP} = -0.4\text{V}$, $V_{DD} = 1.2\text{V}$, $E_{CN} = 6 \cdot 10^4\text{V/cm}$, $E_{CP} = 4E_{CN}$, $L = 100\text{nm}$, $v_{\text{sat}} = 8 \cdot 10^6\text{cm/s}$, $E_{CN}L = 0.6\text{V}$, $|2\phi_F| = 0.88\text{V}$, $\gamma = 0.2\text{V}^{1/2}$, $R_L = 20\text{k}\Omega$) Use NOR gates with a delay of 400ps. The load driven by Q or \bar{Q} is 100fF.

Task 7.7

The circuit in Fig. 7.4 is a saturated-enhancement load NMOS NOR. Calculate V_{OL} and V_{OH} , I_{DC} and power P_{DC} for the output to logical zero. All transistors should be $2\lambda/2\lambda$ circuits. Use a $0.13\mu\text{m}$ technology.

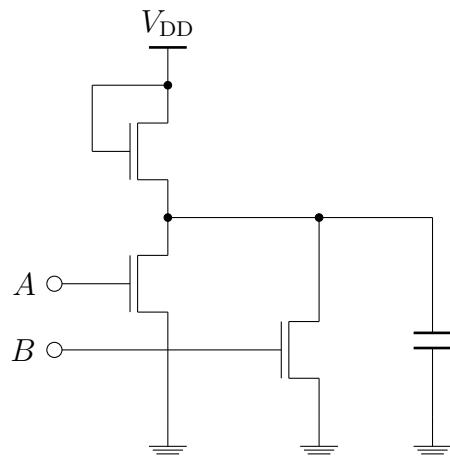


Figure 7.4: Saturated-Enhancement Load NMOS NOR